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|-------------------------------|------------------------|---------------------|--|
| Notice of Allowability | Application No. | Applicant(s) | |
| | 10/620,284 | PACK ET AL. | |
| | Examiner | Art Unit | |
| | Binh C. Tat | 2825 | |

-- **The MAILING DATE of this communication appears on the cover sheet with the correspondence address--**

All claims being allowable, PROSECUTION ON THE MERITS IS (OR REMAINS) CLOSED in this application. If not included herewith (or previously mailed), a Notice of Allowance (PTOL-85) or other appropriate communication will be mailed in due course. **THIS NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT RIGHTS.** This application is subject to withdrawal from issue at the initiative of the Office or upon petition by the applicant. See 37 CFR 1.313 and MPEP 1308.

1. This communication is responsive to 10/31/06.
2. The allowed claim(s) is/are 1-5,23-27,45,47,51 and 53-58.
3. Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f).
 - a) All
 - b) Some*
 - c) None
 1. Certified copies of the priority documents have been received.
 2. Certified copies of the priority documents have been received in Application No. _____.
 3. Copies of the certified copies of the priority documents have been received in this national stage application from the International Bureau (PCT Rule 17.2(a)).

* Certified copies not received: _____.

Applicant has THREE MONTHS FROM THE "MAILING DATE" of this communication to file a reply complying with the requirements noted below. Failure to timely comply will result in ABANDONMENT of this application.
THIS THREE-MONTH PERIOD IS NOT EXTENDABLE.

4. A SUBSTITUTE OATH OR DECLARATION must be submitted. Note the attached EXAMINER'S AMENDMENT or NOTICE OF INFORMAL PATENT APPLICATION (PTO-152) which gives reason(s) why the oath or declaration is deficient.
5. CORRECTED DRAWINGS (as "replacement sheets") must be submitted.
 - (a) including changes required by the Notice of Draftsperson's Patent Drawing Review (PTO-948) attached
 - 1) hereto or 2) to Paper No./Mail Date _____.
 - (b) including changes required by the attached Examiner's Amendment / Comment or in the Office action of Paper No./Mail Date _____.

Identifying indicia such as the application number (see 37 CFR 1.84(c)) should be written on the drawings in the front (not the back) of each sheet. Replacement sheet(s) should be labeled as such in the header according to 37 CFR 1.121(d).
6. DEPOSIT OF and/or INFORMATION about the deposit of BIOLOGICAL MATERIAL must be submitted. Note the attached Examiner's comment regarding REQUIREMENT FOR THE DEPOSIT OF BIOLOGICAL MATERIAL.

Attachment(s)

1. Notice of References Cited (PTO-892)
2. Notice of Draftsperson's Patent Drawing Review (PTO-948)
3. Information Disclosure Statements (PTO/SB/08),
Paper No./Mail Date 01/19/07
4. Examiner's Comment Regarding Requirement for Deposit
of Biological Material
5. Notice of Informal Patent Application
6. Interview Summary (PTO-413),
Paper No./Mail Date 01/19/07.
7. Examiner's Amendment/Comment
8. Examiner's Statement of Reasons for Allowance
9. Other _____.


JACK CHIANG
 SUPERVISORY PATENT EXAMINER

DETAILED ACTION

EXAMINER'S AMENDMENT

An examiner's amendment to the record appears below. Should the changes and/or additions be unacceptable to applicant, an amendment may be filed as provided by 37 CFR 1.312. To ensure consideration of such an amendment, it MUST be submitted no later than the payment of the issue fee.

Authorization for this examiner's amendment was given in a telephone interview with Peter C. Mei (Reg. No. 39,768) on 01/19/07.

The application has been amended as follow:

Claim 1 line 2 deleted "individual".

Claim 1 line 3-6, **change** "generating integrated circuit design data including priority information of each individual mask element; and using at least the priority information for determining interfeature relationships between each individual mask element of the integrated circuit design data to inspect the mask." **to** – generating integrated circuit design data and using information for interfeature relationships of the integrated circuit design data to provide contextual information for elements within the integrated circuit design, the contextual information comprising priority, ordering or inspection parameter information of the mask elements; using the contextual information to guide inspection of the mask, wherein analysis is performed to allocate mask inspection resources commensurate with the design or manufacturing specific context of the elements within the integrated circuit design data; and inspecting the mask using mask inspection resources allocated based upon the contextual information, wherein mask

resources are allocated based upon the contextual information by adjusting the power, size, shape, order, resolution, or timing of an inspection beam.--.

Claims 6-22 have been canceled.

Claim 23 line 2 deleted “individual”.

Claim 23 line 3-6, **change** “means for generating integrated circuit design data including priority information of each individual mask element; and means for using at least the priority information for determining interfeature relationships between each individual mask element of the integrated circuit design data to inspect the mask.” **to** – means for generating integrated circuit design data and using information for interfeature relationships of the integrated circuit design data to provide contextual information for elements within the integrated circuit design, the contextual information comprising priority, ordering or inspection parameter information of the mask elements; means for using the contextual information to guide inspection of the mask, wherein analysis is performed to allocate mask inspection resources commensurate with the design or manufacturing specific context of the elements within the integrated circuit design data; and means for inspecting the mask using mask inspection resources allocated based upon the contextual information, wherein mask resources are allocated based upon the contextual information by adjusting the power, size, shape, order, resolution, or timing of an inspection beam.--.

Claims 28-44 have been canceled.

Claim 46 has been canceled.

Claims 48-50 have been canceled.

Claim 52 has been canceled.

Claim 54 line 2-3, change “each individual mask element relative to each other individual mask” to -- a mask element relative to another mask--.

Claim 55 line 2, change “ each individual mask element” to -- mask elements--.

Claim 56 line 2-3 change “ each individual mask element” to -- mask element--.

Claim 57 line 2, change “ each individual mask element” to -- mask elements--.

Claim 58 line 2 change “ each individual mask element” to -- mask element--.

Claim 59 has been canceled.

Reasons for Allowance

The following is an examiner's statement of reasons for allowance:

1. Claims 1-5, 23-27, 45, 47, 51, and 53-58 are allowed because the prior art does not teach or suggest a method for inspecting a mask having a plurality of mask element, the method comprising: using the contextual information to guide inspection of the mask, wherein analysis is performed to allocate mask inspection resources commensurate with the design or manufacturing specific context of the elements within the integrated circuit design data; and inspecting the mask using mask inspection resources allocated based upon the contextual information, wherein mask resources are allocated based upon the contextual information by adjusting the power, size, shape, order, resolution, or timing of an inspection beam and combination of all other features corresponding to the independent claims.
2. Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance".

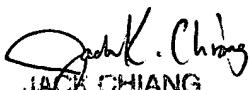
Conclusion

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Binh C. Tat whose telephone number is 571 272-1908. The examiner can normally be reached on 7:30 - 4:00 (M-F).

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Jack Chiang can be reached on 571 272-7483. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see <http://pair-direct.uspto.gov>. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

Tat Binh
Patent Examiner
January 19, 2007


JACK CHIANG
SUPERVISORY PATENT EXAMINER